WHAT IS CLAIMED IS:

1. A phase shift mask, comprising:

a substrate having an engraved portion and a non-engraved portion, said engraved portion having a side wall and a bottom face; and

a light blocking film provided in a portion of the bottom face and the side wall of said engraved portion,

wherein the size to be defined by subtracting a thickness of the light blocking film at the side wall from a width of said engraved portion is equal to 1.3 to 2.4 times the width of a light transmitting portion provided at said engraved portion.

2. A phase shift mask according to Claim 1, wherein the size to be defined by subtracting a thickness of the light blocking film at the side wall from a width of said engraved portion is equal to 1.4 to 1.8 times the width of a light transmitting portion provided at said engraved portion.

3. A phase shift mask according to Claim 1, wherein the thickness of the light blocking film provided at the side wall of said engraved portion is equal to 1/20 to 3/5 times the width of the

light transmitting portion provided at said engraved portion.

4. A phase shift mask according to Claim 2, wherein the thickness of the light blocking film provided at the side wall of said engraved portion is equal to 7/20 to 11/20 times the width of the light transmitting portion provided at said engraved portion.

5. A phase shift mask according to Claim 1, wherein the width of said engraved portion is equal to 2.5 times or more the width of the light transmitting portion provided at said engraved portion.

6. A phase shift mask according to Claim 1, wherein a depth of said engraved portion is determined so that a phase difference, corresponding to a product of 180 deg. by an odd number, is produced between light from the light transmitting portion of said engraved portion and light from said non-engraved portion.

7, A phase shift mask according to Claim 1, wherein the light transmitting portion provided at said engraved portion and a light transmitting

portion defined at said non-engraved portion have a line-like shape.

8. An exposure method, comprising the steps of:

preparing a phase shift mask;

illuminating the phase shift mask; and

projecting a pattern of the phase shift mask onto a substrate,

wherein the phase shift mask includes (i) a substrate having an engraved portion and a non-engraved portion, the engraved portion having a side wall and a bottom face, and (ii) a light blocking film provided in a portion of the bottom face and the side wall of the engraved portion, wherein the size to be defined by subtracting a thickness of the light blocking film at the side wall from a width of the engraved portion is equal to 1.3 to 2.4 times the width of a light transmitting portion provided at the engraved portion.

9. A device manufacturing method, comprising the steps of:

preparing a phase shift mask;

illuminating the phase shift mask;

projecting a pattern of the phase shift

mask onto a substrate; and

developing the substrate,

wherein the phase shift mask includes (i) a substrate having an engraved portion and a non-engraved portion, the engraved portion having a side wall and a bottom face, and (ii) a light blocking film provided in a portion of the bottom face and the side wall of the engraved portion, wherein the size to be defined by subtracting a thickness of the light blocking film at the side wall from a width of the engraved portion is equal to 1.3 to 2.4 times the width of a light transmitting portion provided at the engraved portion.